## **CreaVac PVD AG - Sputter Coater**





## Description

Our state-of-the-art sputtering system combines the power of multiple PVD (Physical Vapor Deposition) techniques to deliver exceptional flexibility and precision. Designed for advanced R&D, prototyping, and small-batch production, this system is ideal for depositing highfilms quality thin making it an indispensable tool for modern materials science and engineering.

A wide variety of substrates including silicon, glass, metal foils, ceramics, and polymers, enable research related to microelectronics & semiconductors, optics & photonics, energy technologies, surface engineering, material science studies and prototype device fabrication.

The integration of the system into a glovebox environment, provides a controlled inert atmosphere - crucial for the deposition of air- and moisture-sensitive materials and ensures reproducible, contamination-free results.

## **Specifications**

- Dual DC Power Sources 2" and 4".
- Dual RF Power Sources 2".
- Simultaneous Multi-Source Sputtering.
- Reactive Sputtering Capability.
- Supports Conductive and Non-Conductive Targets.
- 4" Substrate Holder.
- Substrate heating up to 800 °C.
- High-Frequency (HF) Reverse Bias.



## Publications

- [1] Y.J.Zhan, *et al.* Magnetron sputtering amorphous carbon coatings on metallic lithium: Towards promising anodes for lithium. Journal of Power Scurces **266**, 43-50 (2014).
- [2] Lipoing Wang, et al. Long lifespan lithium metal anodes enabled by Al2O3 sputter coating. Energy Storage Material 10, 16-23 (2018).
- [3] Saut Pat, et al. The transparent all-solid-state rechargeable micro-battery manufacturing by RF magnetron sputtering. Journal of Alloys and Compounds 713, 64-68 (2017).





